

Peer Review

Review of: "Negative Capacitance Effect at the Interface Between Si Wafers with Undulating Surfaces"

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The work is interesting, but it should be revised in depth as follows:

1. The abstract doesn't reflect the findings of the work.
2. The introduction doesn't contain sufficient bibliography and doesn't present clearly the main purpose of the work.
3. The experimental section is not well presented. Details about any experiment conducted in this paper should be given in detail. Exp. The use of impedance spectroscopy, as well as SEM images, measurement of current...etc.
4. In the results and discussion, the authors should explain the results according to the literature.
5. The authors should explain the applications for such findings.
6. The difference with the NC observed in other materials can be addressed to enhance the work.
7. What is the physical significance of this phenomenon?
8. The curves should be fitted according to the given equation to verify the reproducibility of the discussion.
9. What do the authors mean by infinite resistance and how to explain the contradiction from the value given in the Cole-Cole diagrams?
10. Be explicit in the conclusion.

Declarations

Potential competing interests: No potential competing interests to declare.